

ABSTRACT

To provide a polishing composition which allows
high-speed polishing while etching and erosion are
5 prevented and the flatness of metal film is maintained,
there is provided a a polishing composition, comprising
(A) a compound having three or more azole moieties, (B)
an oxidizing agent, and (C) one or more species selected
from among an amino acid, an organic acid, and an
10 inorganic acid.